

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: BAILEY III et al.

Attorney Docket No.:
LAM1P124D1/P0558

Application No.: Not Yet Assigned

Examiner: Unknown

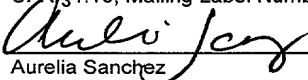
Filed: Herewith

Group: Unknown

Title: TEMPERATURE CONTROL SYSTEM
FOR PLASMA PROCESSING APPARATUS

CERTIFICATE OF EXPRESS MAILING

I hereby certify that this paper and the documents and/or fees referred to as attached therein are being deposited with the United States Postal Service on August 30, 2001 in an envelope as "Express Mail Post Office to Addressee" service under 37 CFR §1.10, Mailing Label Number **EL631005993US**, addressed to the Commissioner for Patents, Washington, DC 20231.


Aurelia Sanchez

PRELIMINARY AMENDMENT

Commissioner for Patents
Washington, DC 20231

Sir:

Prior to an Office Action on the merits, please amend the above-identified patent application as follows:

IN THE SPECIFICATION:

Please **REPLACE** the section "CROSS-REFERENCE TO RELATED CASES" (page 1, lines 5-27) with the following replacement section "CROSS-REFERENCE TO RELATED APPLICATIONS." A marked-up version showing changes made is included herewith.

CROSS-REFERENCE TO RELATED APPLICATIONS

This is a Divisional application of co-pending prior U.S. Application No. 09/439,675 (Att. Dkt. No.: LAM1P124/P0558), entitled "TEMPERATURE CONTROL SYSTEM FOR PLASMA PROCESSING APPARATUS," filed on November 15, 1999, the disclosure of which is incorporated herein by reference.

This application also claims the benefit of U.S. Provisional Application No. 60/165,496 (Att. Dkt. No.: LAM1P124P/P0558P), entitled "PROCESSING CHAMBER WITH TEMPERATURE CONTROL," filed November 15, 1999, and incorporated herein by reference. This application is also related to the following U.S. Patent Applications:

- i) Application No.: 09/439,661, entitled "IMPROVED PLASMA PROCESSING SYSTEMS AND METHODS THEREFOR" (Attorney Docket No.: LAM1P122/P0527), filed November 15, 1999.
- ii) Application No.: 09/470,236, entitled "PLASMA PROCESSING SYSTEM WITH DYNAMIC GAS DISTRIBUTION CONTROL" (Attorney Docket No.: LAM1P123/P0557), filed November 15, 1999.
- iii) Application No.: 09/440,418, entitled "METHOD AND APPARATUS FOR PRODUCING UNIFORM PROCESS RATES" (Attorney Docket No.: LAM1P125/P0560), filed November 15, 1999.
- iv) Application No.: 09/440,794, entitled "MATERIALS AND GAS CHEMISTRIES FOR PLASMA PROCESSING SYSTEMS" (Attorney Docket No.: LAM1P128/P0561-1), filed November 15, 1999.
- v) Application No.: 09/439,759, entitled "METHOD AND APPARATUS FOR CONTROLLING THE VOLUME OF PLASMA" (Attorney Docket No.: LAM1P129/P0561-2), filed November 15, 1999.

Each of the above-identified patent applications is incorporated herein by reference.

REMARKS

The CROSS-REFERENCE TO RELATED CASES section has been updated by replacement section. A marked-up version of the replacement section showing changes made is attached hereto.

Respectfully submitted,
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CROSS-REFERENCE TO RELATED [CASES] APPLICATIONS

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